## CENTRE FOR LASERS AND PHOTONICS Indian Institute of Technology Kanpur

## Thin Film Deposition-RF/DC Magnetron Sputtering System Facility Photonics Laboratory (SL-116) Phone-0512-259-7712

Please fill all the details in the appropriate box:

Source	Mark appropriate box	Description of material to be deposited	Description of substrate material	Desired film thickness	Process parameters like temperature and pressure range	
RF sputtering						
DC sputtering						
Pulsed DC sputtering						
Type of deposit Number of depo		ingle film		Sequential fi	lm	
Presently availa		$O_2$ and $SiO_2$				
Name of the user:		E-mail:		Phone:		
Date:		Supervisor's name:				
Kindly transfer	Rs	to CELP LDA Pr	oject no. IITK /Cl	ELT/2014160.		
				_(MM/YY)		
Signature of supervisor		Project account no.	Project valid	ity	Signature of HOD	
				(If payn	nent is by the department)	
		For	lab use			
Job no.			т	otal charges:		
Date and time allotted:			C	perator's name:		
Job completed on date:			(	Operator's signature:		
			τ	Jser's signature:		

User charges: (after the required vacuum level is reached)

For dielectric oxides: Minimum slot: 1 hour. <u>Single film deposition</u>- Rs. 1500 per hour (Rs. 1000 per hour if the user brings the target). <u>Sequential/multilayer film deposition</u>- Rs. 2000 per hour (Rs. 1500 per hour if the user brings the targets).

For metals: No minimum time limit. Rs. 1000 per deposition (targets have to be brought by the user).